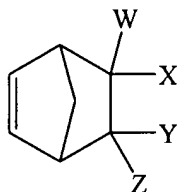


AMENDMENTS TO THE CLAIMS

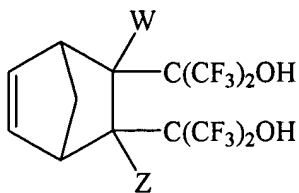
1. (Currently Amended): A compound according to the formula:



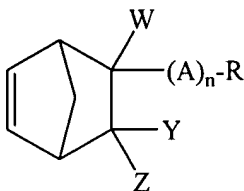
wherein W, X, Y, and Z are independently selected from the group consisting of hydrogen, fluorine, hydroxyl, substituted and unsubstituted alkyl, substituted and unsubstituted fluoroalkyl, provided that: (i) at least one of W, X, Y, and Z is fluorine or a group comprising fluorine, (ii) W, X, Y, and Z are not all the same moiety, (iii) when W and X are both hydrogen, Y and Z are not both hydroxyl, both fluorine, or both alkyl, (iv) when W and Z are both hydrogen or both fluorine, X and Y are not both hydroxyl, (v) when W, X, and Y are all hydrogen, Z is ~~neither~~ not alkyl, ~~nor~~ hydroxyl, or a 1,1-trifluoromethyl-1-hydroxyl moiety having an unsubstituted alkyl chain, (vi) when X and Y are both H, and W is CH₂OH, Z is not C₃F₇ or CF₃; and (vii) when W is hydrogen and X is hydroxyl, Y and Z are not both fluorine.

2. (Currently Amended): A The compound of claim 1 selected from the group consisting of compounds described by the formulae (a)-(c) below:

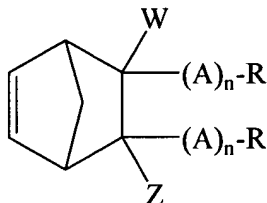
(a)



(b)

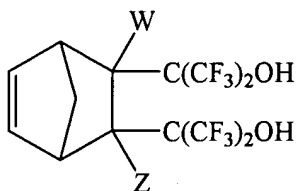


(c)



wherein W, X, Y, and Z are independently selected from the group consisting of hydrogen, fluorine, hydroxyl, substituted and unsubstituted alkyl, substituted and unsubstituted fluoroalkyl; each A is independently CH₂ or CF₂, provided that at least one A is CF₂; each n is independently from about 0 to about 15; and each R is independently hydrogen, fluorine, trifluoromethyl, hydroxyl, or -C(CF₃)₂OH.

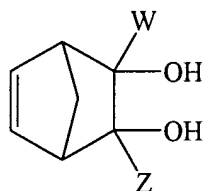
3. (Original): The compound of claim 2 wherein said compound is described by the formula:



wherein W and Z are independently hydrogen or trifluoromethyl.

4. (Original): The compound of claim 3 wherein W and Z are the same moiety.

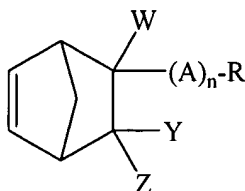
5. (Original): The compound of claim 2 wherein said compound is described by the formula:



wherein W and Z are independently substituted or unsubstituted fluoroalkyl.

6. (Original): The compound of claim 5 wherein W and Z are the same moiety.

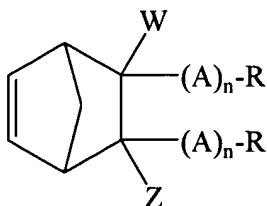
7. (Currently Amended): The compound of claim 2 wherein said compound is further described by the formula:



wherein:

W, Y, and Z are independently hydrogen, fluorine, trifluoromethyl, or -C(CF₃)₂OH; ~~each A is independently CH₂ or CF₂~~; each n is independently from about 0 to about 15; and R is hydrogen, fluorine, trifluoromethyl, hydroxyl, or -C(CF₃)₂OH.

8. (Original): The compound of claim 7 wherein R is -C(CF₃)₂OH.
9. (Original): The compound of claim 8 wherein n = 0, and Y and Z are trifluoromethyl.
10. (Original): The compound of claim 7 wherein W and Z are the same moiety selected from the group consisting of hydrogen, fluorine, and trifluoromethyl.
11. (Original): The compound of claim 7 wherein W, Y, and Z are all the same moiety selected from the group consisting of hydrogen, fluorine, and trifluoromethyl.
12. (Currently Amended): The compound of claim 2 wherein said compound is further described by the formula:



wherein:

W and Z are independently hydrogen, fluorine, trifluoromethyl, or $-\text{C}(\text{CF}_3)_2\text{OH}$; each A is independently CH_2 or CF_2 ; each n is independently from about 1 to about 15; and each R is independently hydrogen, fluorine, trifluoromethyl, hydroxyl, or $-\text{C}(\text{CF}_3)_2\text{OH}$.

13. (Original): The compound of claim 12 wherein W and Z are the same moiety selected from the group consisting of hydrogen, fluorine, and trifluoromethyl.
14. (Original): The compound of claim 12 wherein the two $-(\text{A})_n\text{-R}$ groups are both $-(\text{A})_n\text{-C}(\text{CF}_3)_2\text{OH}$ groups.
15. (Original): A polymer comprising at least one repeating unit derived from a monomer compound according to claim 1.
16. (Original): The polymer according to claim 15, further comprising one or more repeating units derived from a compound selected from the group consisting of

bicyclo[2.2.1]hept-5-ene-2-(1,1,1-trifluoro-2-trifluoromethylpropan-2-ol) (NBHFA),
CF₂=CF₂, CF₂=CH₂, CF₂=CFCl, CF₂=CHF, CF₃CH=CF₂, CF₃CH=CHF, CF₃CF=CHF,
CF₃CF=CH₂, compounds of the formula R_f(CH₂)_nCX_f=CX_fY_f wherein R_f is a
perfluoroalkyl group having from about 1 to about 10 carbon atoms, X_f and Y_f are
independently H or F, provided that when R_f is CF₃ and X_f is F, Y_f must be H, and
mixtures of two or more thereof.

17. (Original): A photoresist composition comprising a polymer according to
claim 15.

18. (Original): A photoresist composition comprising a polymer according to
claim 16.

19. (Original): The photoresist composition of claim 18 further comprising a
solvent and a photoinitiator.

20. (Original): The photoresist composition of claim 19 further comprising a
dissolution inhibitor.

21. (Original): The photoresist composition of claim 20 further comprising a
sensitizer.

22. (Original): A method for generating a positive tone resist image on a substrate comprising the steps of coating a substrate with a film comprising a photoresist composition of claim 17, exposing the film to radiation, and developing the image.

23. (Original): An integrated circuit assembly comprising a circuit formed by the steps of coating a substrate with a film comprising a photoresist composition of claim 17, exposing the film to radiation, developing the image to expose the substrate, and forming a circuit on the substrate.

24. (Original): An optical wave guide comprising a polymer according to claim 15.

25. (Original): An anti-reflective coating comprising a polymer according to claim 15.

26. (Original): A pellicle comprising a polymer according to claim 15.